

U.S. Department of Commerce, Patent and Trademark Office  
(PTO Form 1449 modified)

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY  
APPLICANT**

(Use several sheets if necessary)

Examiner Dung Anh Le

Sheet 1 of 2 sheet(s)

Docket No.	Serial No.
AMAT/6392/DSM/LO W KJW	10/010,950
Applicant	Confirmation No.:
Xia, et al.	5694
Filing Date	Group
November 13, 2001	2818

**U.S. Patent Documents**

*Examiner Initial	Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
DAL	A1 6,465,366	10/15/2002	Nemanji, et al.	438	778	09/12/2000
	A2 5,926,740	07/20/1999	Forbes, et al.	438	763	10/27/1997
	A3 5,876,891	03/02/1999	Takimoto, et al.	430	71	05/26/1995
	A4 5,710,067	01/20/1998	Foote, et al.	437	238	06/07/1995
	A5 5,638,251	06/10/1997	Goel, et al.	361	313	10/03/1995
	A6 5,607,773	03/04/1997	Ahlburn, et al.	428	427	12/20/1994
	A7 5,494,712	02/27/1996	Hu, et al.	427	589	11/17/1997
	A8 5,465,680	11/14/1995	Loboda	117	84	07/01/1993
	A9 5,242,530	09/07/1993	Batey, et al.	156	613	08/05/1991
	A10 5,224,441	07/06/1993	Feits, et al.	118	718	09/27/1991
	A11 5,011,706	04/30/1991	Tarhay, et al.	427	39	04/12/1989
	A12 4,759,947	07/26/1988	Ishihara, et al.	427	38	10/04/1985
DAL	A13 4,532,150	07/30/1985	Endo, et al.	427	39	12/22/1983

**Foreign Patent Documents**

*Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation
DAL	B1 09-008031	01/10/1997	JP	H01L	21/316	<input type="checkbox"/> YES <input checked="" type="checkbox"/> NO
	B2 00/19498	04/06/2000	WO	H01L	21/027	<input type="checkbox"/> YES <input checked="" type="checkbox"/> NO
	B3 1 176 226	01/30/2002	EP	C23C	16/32	<input type="checkbox"/> YES <input checked="" type="checkbox"/> NO

**OTHER ART**

*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.	
DAL	U.S. Patent Application No. 09/270,039, filed on March 16, 1999.	
	Written Opinion from PCT/US99/22424, dated April 5, 2001.	
	PCT Partial International Search Report for US99/22317 dated March 21, 2000.	Date Considered MAR - 2004

Examiner  
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Examiner <i>Dle</i>	Dung Anh Le		

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**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
<i>Dle</i>	A1	2003/0139035	07/24/2003	Yim, et al.	438	643	09/19/2002
	A2	2003/0129827	07/10/2003	Lee, et al.	438	629	07/15/2002
	A3	2003/0111730	06/19/2003	Takeda, et al.	257	758	05/28/2001
	A4	2003/0089988	05/15/2003	Matsuura	257	758	08/13/2002
	A5	2003/0003765	01/02/2003	Gibson, Jr. et al.	438	760	01/02/2002
	A6	2003/0001282	01/02/2003	Meynen, et al.	257	777	06/25/2002
	A7	2002/0111042	08/15/2002	Yau, et al.	438	789	11/15/2001
<i>Dle</i>	A8	2002/0093075	07/15/2002	Gates, et al.	257	531	01/14/2002
	A9						
	A10						
	A11						

**OTHER ART**

*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.	
<i>Dle</i>	C4	PCT International Search Report for US99/22425 dated February 11, 2000.
	C5	Dijkstra, et al. "Optimization of Anti-Reflection Layers for Deep UV Lithography", Proceeding of SPIE Optica/Laser Microlithography, Bellingham, SPIE, Volume 1674, (1992) Pages 362-375.
	C6	Omar, M.A. "Elementary Solid State Physics: Principles and Applications," Lowell Technological Institute, Addison-Wesley Publishing Company, 1975, Pages 124 & 125.
	C7	Fukuda, et al. "Highly Reliable SiOF Film Formation by ECR-CVD using SiF <sub>2</sub> H <sub>2</sub> ", (1996) Symposium on VLSI Technology Digest of Technical Papers, IEEE, Pages 114-115.
	C8	PCT International Search Report for US/02/40034, dated May 19, 2003.
<i>Dle</i>	C9	Wu, et al, "Advanced Metal Barrier Free Cu Damascene Interconnects with PECVD Silicon Carbide Barriers for 90/65-nm BEOL Technology", 2002 IEEE Pages 595-598.
Examiner	<i>Dle</i>	Date Considered <i>Nov - 2004</i>
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<i>Dle</i>	A1	6,147,009	11/14/2000	Grill, et al.	438	780	06/29/1998
	A2	6,054,379	04/25/2000	Yau, et al.	438	623	02/11/1998
	A3						
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	A11						
	A12						
	A13						

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
<i>Dle</i>	B1	1 107 303	06/13/2001	EP	H01L	21/316	<input type="checkbox"/>	<input checked="" type="checkbox"/>
<i>Dle</i>	B2	99/41423	08/29/1999	WO	C23C		<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B3						<input type="checkbox"/>	<input type="checkbox"/>

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<i>Dle</i>	C1	PCT International Search Report for US/02/36229 dated 09/03/2003 (AMAT/6392.PC)
	C2	
	C3	

Examiner

*Dle*

Date Considered

Mar - 2004

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<i>DAL</i>	A1	6,555,476 B1	04/29/2003	Olsen, et al.	438	692	12/21/1998
	A2	6,500,773	12/31/2002	Gaillard, et al.	438	790	11/27/2000
	A3	2003/0085408 A1	05/08/2003	Yang, et al.	257	77	11/02/2001
	A4						
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	A11						
	A12						
	A13						

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							YES	NO
<i>DAL</i>	B1	199 04 311 A1	08/12/1999	Germany	C23C	16/44	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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	B3						<input type="checkbox"/>	<input type="checkbox"/>

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	C1		
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	C3		
Examiner <i>DAL</i>	Date Considered <i>3/2004</i>		

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